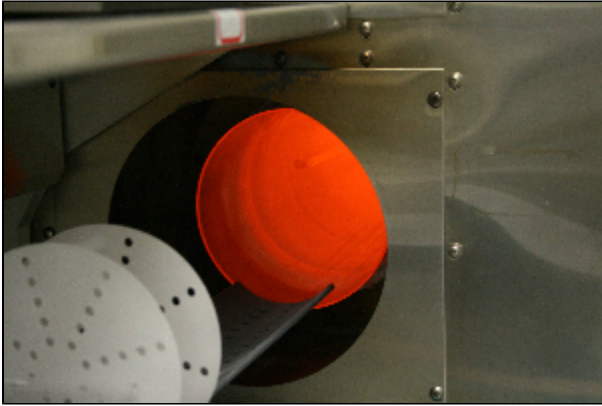


Thermal & Implant



Rapid Thermal Anneal

AG 610A RTP

- Annealing of clean MOS grade silicon wafers

Furnaces

Bruce Tube 1

- Used for wet oxidation of silicon substrates

Bruce Tube 2

- Used for diffusion of p-type dopants

Bruce Tube 3

- Used for diffusion of n-type dopants

Bruce Tube 4

- Used for dry oxidation of silicon substrates

Bruce Tube 5

- Fitted with external torch for low temp wet oxide growth

Bruce Tube 6

- Used for wet oxidation of silicon substrates

Bruce Tube 7

- Used for anneals & wet oxide growth

Bruce Tube 8

- Used for high temperature anneals

Implant

Varian 350D Implanter

- Used for implantation of boron and phosphorous

Ovens

Heraeus Vacuum Oven

- Used for heat treatment of substrates under vacuum

Blue M Ovens

- Used for heat treatment of substrates.

Other Information